18:05

Attorney Docket: 081468-0275503 Client Reference: P-0166.010-US

> REPLY UNDER 37 C.F.R. §1.116 EXPEDITED PROCEDURE **TECHNOLOGY CENTER ART UNIT 2882**

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re PATENT APPLICATION of:

Confirmation Number: 4742

CASTENMILLER et al.

Group Art Unit: 2882

Ok to

Application No.: 09/739,622

Examiner: Ho, Allen

enter ACH

Filed: December 20, 2000

Title: POSITION MEASURING SYSTEM FOR USE IN LITHOGRAPHIC APPARATUS

(As Amended)

22.04.2004

AMENDMENT AFTER FINAL REJECTION UNDER 37 C.F.R. §1.116

Mail Stop Amendment After Final Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

RECEIVED

APR 1 3 2004

Sir:

Technology Center 2800

In response to the Office Action dated January 30, 2004, please amend the aboveidentified application as follows:

IN THE CLAIMS:

This listing of claims will replace all prior versions, and listings, of claims in the application:

- (Currently amended) A lithographic projection apparatus comprising: 1.
 - a projection beam illumination system which supplies a projection beam of radiation;
- a first object table for holding a protection beam patterning device which patterns the projection beam according to a desired pattern;
 - a second object table for holding a substrate; and
- a projection system which images the patterned beam onto a target portion of the substrate;

a reference frame; and